

ABSTRACT

The present disclosure provides a chamber structure for clearing waste in polishing pad grooves, wherein the chamber structure is provided, in its interior, with a cleaning chamber and a vacuum suction chamber that are independent of each other; the chamber structure is provided, on its outer wall, with a cleaning chamber interface connected to the cleaning chamber and a vacuum suction interface connected to the vacuum suction chamber; the cleaning chamber interface is suitable for connecting to a cleaning device to allow a cleaning medium to enter the cleaning chamber; the vacuum suction interface is suitable for connecting to a vacuum suction device to suck out the cleaning medium in the vacuum suction chamber; the chamber structure is further provided, at its bottom, with a lower cavity; bottom opening of the lower cavity is suitable for being sealed by upper surface of a polishing pad; and the chamber structure is further provided, in its interior, with cleaning holes connecting the lower cavity and the cleaning chamber, and vacuum suction holes connecting the lower cavity and the vacuum suction chamber. The waste in the grooves on the upper surface of the polishing pad can be sucked out from the upper surface of the polishing pad after being broken down.

[Fig. 6]